

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: HAMADA, Yoshitaka et al Conf.:
Appl. No.: NEW Group:
Filed: March 25, 2004 Examiner:
For: POROUS FILM, COMPOSITION AND
MANUFACTURING METHOD, INTERLAYER
DIELECTRIC FILM, AND SEMICONDUCTOR DEVICE

PRELIMINARY AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

March 25, 2004

Sir:

The following preliminary amendments and remarks are respectfully submitted in connection with the above-identified application.

This amendment includes:

Amendments to the Specification

Remarks